

DRAM-based On-Chip Cache Architectures to Combat Process Variations

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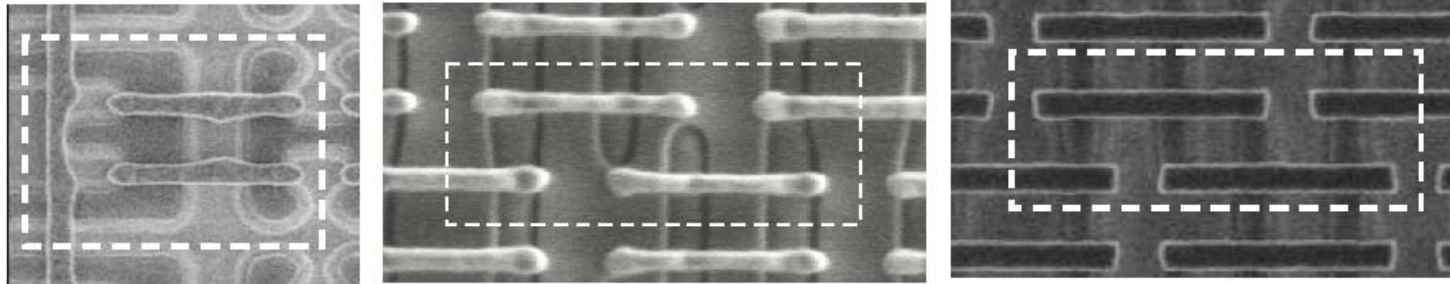


Overview

- **Impact of process variations (PV) is becoming increasingly important.**
- **Traditional 6T-based SRAM structures are especially sensitive to PV.**
- **We propose to replace SRAM by DRAM in L1-data cache.**

Using architecture solutions to solve the PV problem in circuit and device !!

PV Impact on 6T SRAMs



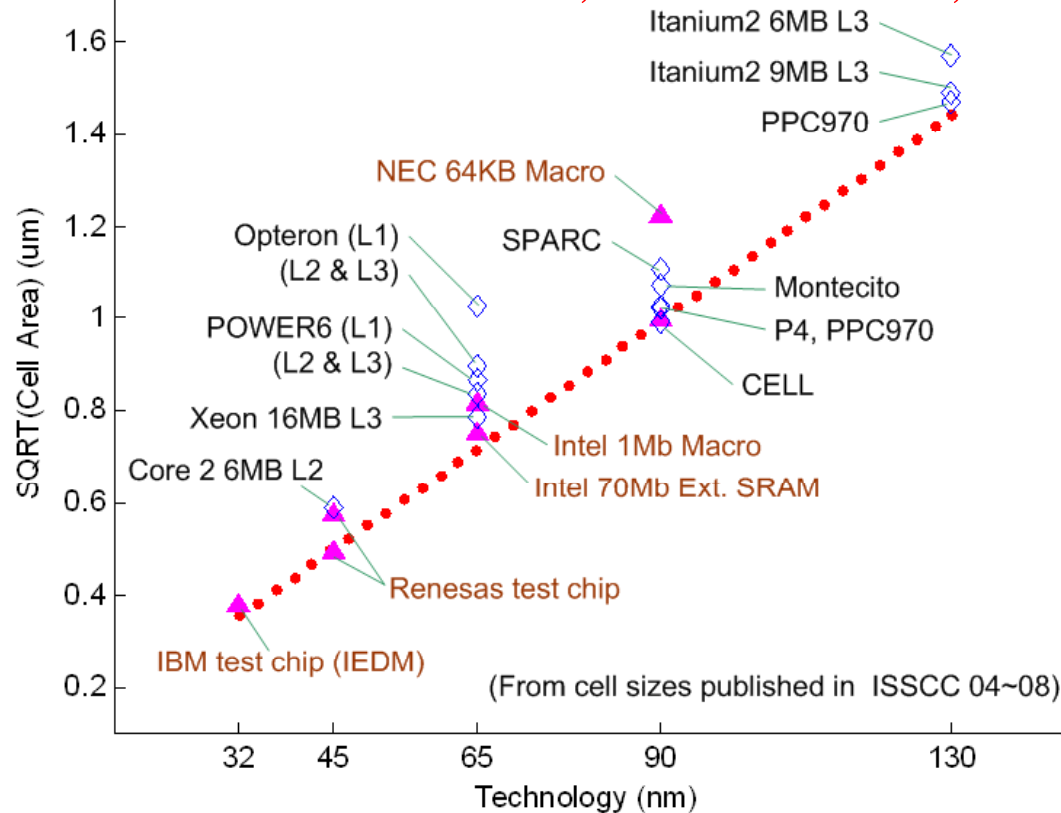
Intel SRAM cell size scaling (IEDM'07)

90nm – tall
1.0 μm^2

65nm – wide
0.57 μm^2

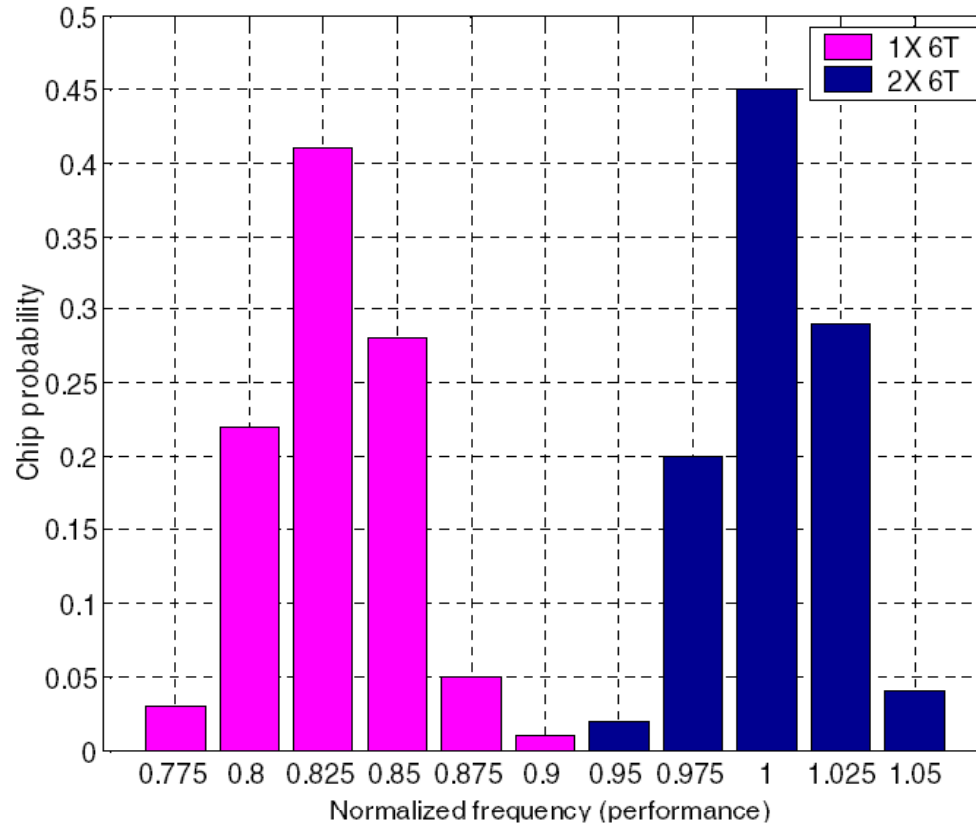
45nm – wide
w/ patterning enhancement 0.346 μm^2

Deviation from Ideal Scaling: 90nm-> 0%, 65nm->14%, 45nm->39%
Equal Die Size Cache: 90nm 1MB, 65nm 1.75MB, 45nm 2.89MB



6T SRAM Performance

- **Process variation → access time variations**
 - Limits frequency across entire system under typical variations

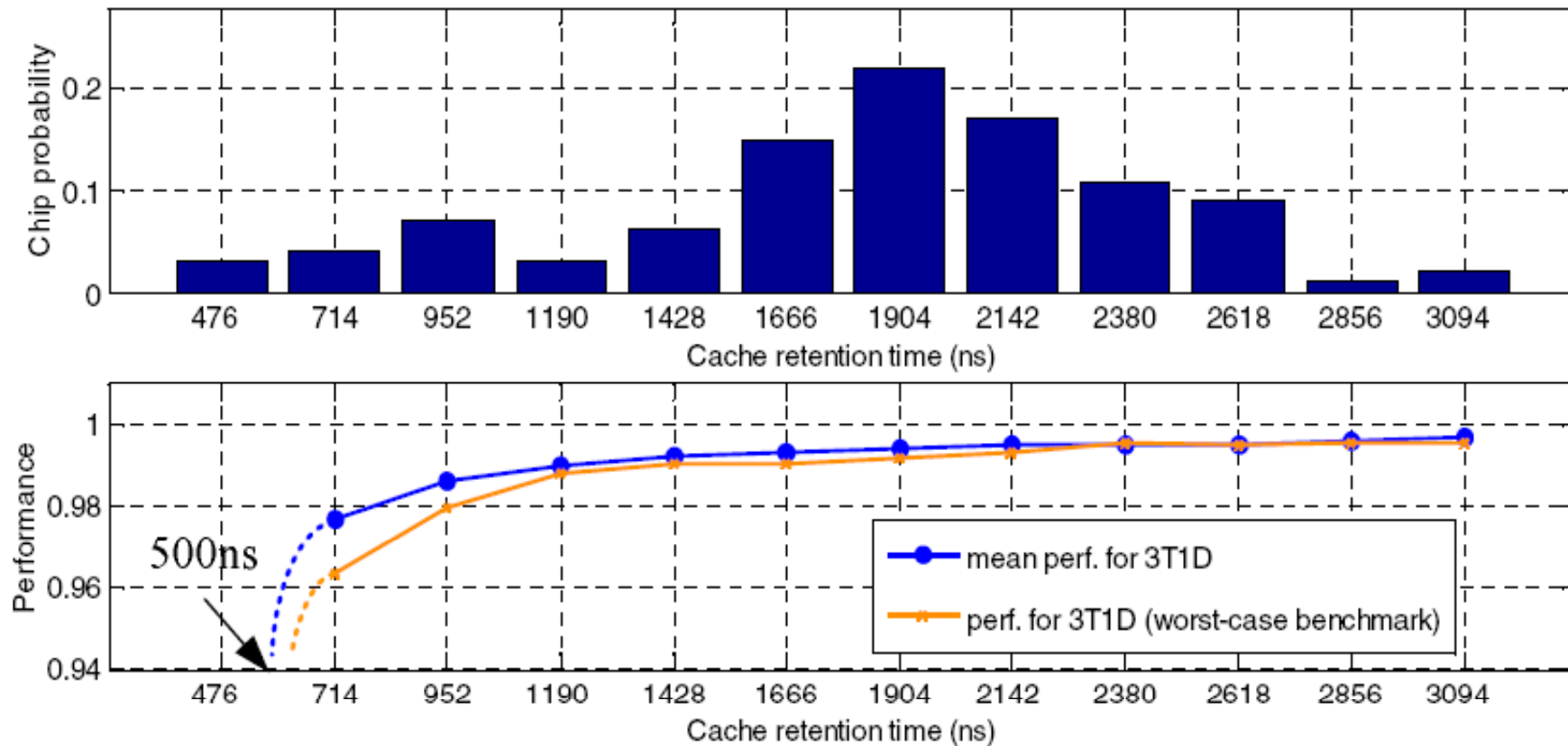


→ Large Performance loss under severe variations (64% line failure)

3T1D w/ Typical Variations

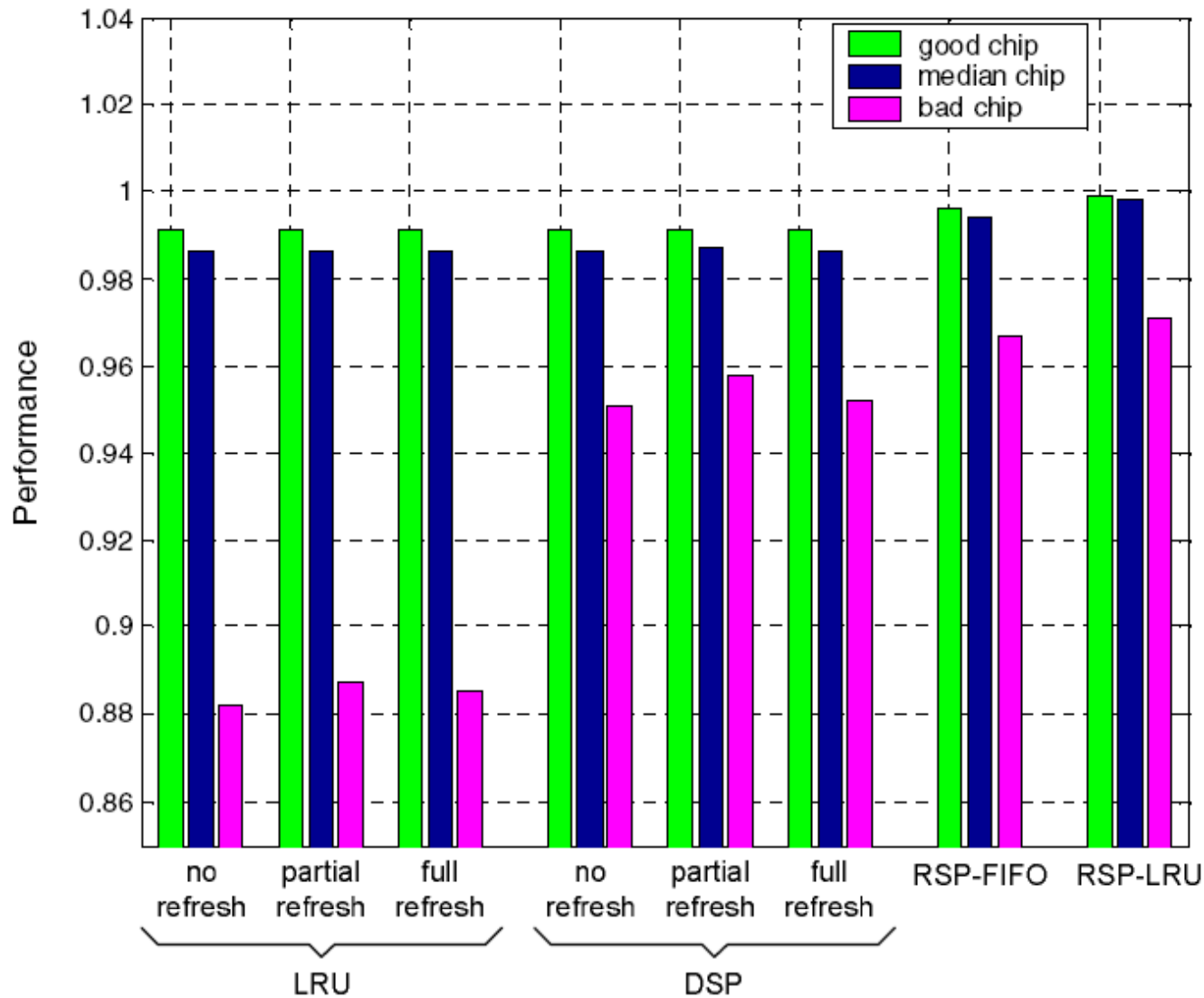
$\sigma L/L_{\text{nominal}}$ (WID)	5%
$\sigma V_{\text{th}}/V_{\text{th}}$ (WID)	10%
$\sigma L/L_{\text{nominal}}$ (D2D)	5%

- Process variation \rightarrow retention time variations
 \rightarrow Small performance loss



3T1D w/ Severe Variations

$\sigma L/L_{\text{nominal}}$ (WID)	7%
$\sigma V_{\text{th}}/V_{\text{th}}$ (WID)	15%
$\sigma L/L_{\text{nominal}}$ (D2D)	5%



2-way approach:

1) Line refresh

No, partial, full

2) Smart line placement

DSP: Dead Sensitive Policy

RSP: Refresh Sensitive Policy

Even under sever variations, ALL chips perform within 5% of the optimal!!